

	L #	Hits	Search Text	DBs
1	L1	489810	resist or photoresist or photosensitiv\$8 or photopolymer\$8 or (photo or light or uv or ultraviolet) adj (sensitiv\$8 or polymer or polymeriz\$8 or polymeris\$8)	US-PGPUB; USPAT
2	L2	309940	(first or second or two or additional\$6 or subsequent\$6) near3 (expos\$6 or radiat\$6 or irradiat\$6 or lithograph\$8 or photolithograph\$8 or mask or photomask or reticle)	US-PGPUB; USPAT
3	L3	1801	360/126.ccls.	US-PGPUB; USPAT
4	L4	399	29/603.07.ccls.	US-PGPUB; USPAT
5	L5	12285	((magnetic or mr or magneto or magnetoresist\$8) adj2 head).ti,ab.	US-PGPUB; USPAT
6	L6	1217752	width	US-PGPUB; USPAT
7	L7	12874	3 or 4 or 5	US-PGPUB; USPAT
8	L9	1311	1 with 2 with 6	US-PGPUB; USPAT
9	L10	73	7 and 9	US-PGPUB; USPAT
10	L11	942197	frame	US-PGPUB; USPAT
11	L12	365	1 with 2 with 11	US-PGPUB; USPAT
12	L13	41	7 and 12	US-PGPUB; USPAT
13	L14	31	13 not 10	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
14	L16	265	sasaki-yoshitaka.in.	US-PGPUB; USPAT
15	L17	20	ishizaki-kazuo.in.	US-PGPUB; USPAT
16	L18	100	kamigama-takehiro.in.	US-PGPUB; USPAT
17	L19	261	5 and (16 or 17 or 18)	US-PGPUB; USPAT
18	L20	63075	(resist or photoresist or photosensitiv\$8 or photopolymer\$8 or (photo or light or uv or ultraviolet) adj (sensitiv\$8 or polymer or polymeriz\$8 or polymeris\$8)).ti,ab.	US-PGPUB; USPAT
19	L21	25	19 and 20	US-PGPUB; USPAT
20	L22	98310	(magnetic or mr or magneto or magnetoresist\$8) adj2 head	EPO; JPO; DERWE NT; IBM_TDB
21	L23	427555	resist or photoresist or photosensitiv\$8 or photopolymer\$8 or (photo or light or uv or ultraviolet) adj (sensitiv\$8 or polymer or polymeriz\$8 or polymeris\$8)	EPO; JPO; DERWE NT; IBM_TDB
22	L24	80772	(first or second or two or additional\$6 or subsequent\$6) near3 (expos\$6 or radiat\$6 or irradiat\$6 or lithograph\$8 or photolithograph\$8 or mask or photomask or reticle)	EPO; JPO; DERWE NT; IBM_TDB
23	L26	8388	23 with 24	EPO; JPO; DERWE NT; IBM_TDB

	L #	Hits	Search Text	DBs
24	L27	632533	width	EPO; JPO; DERWE NT; IBM_TDB
25	L28	241	26 with 27	EPO; JPO; DERWE NT; IBM_TDB
26	L30	7	22 and 28	EPO; JPO; DERWE NT; IBM_TDB
27	L31	1133569	frame	EPO; JPO; DERWE NT; IBM_TDB
28	L32	63	26 with 31	EPO; JPO; DERWE NT; IBM_TDB
29	L33	4	22 and 32	EPO; JPO; DERWE NT; IBM_TDB
30	L35	2315550	plat\$4	EPO; JPO; DERWE NT; IBM_TDB

	L #	Hits	Search Text	DBs
31	L36	523	26 with 35	EPO; JPO; DERWE NT; IBM_TDB
32	L37	10	22 and 36	EPO; JPO; DERWE NT; IBM_TDB
33	L39	9549	track near2 width	EPO; JPO; DERWE NT; IBM_TDB
34	L40	12	22 and 26 and 39	EPO; JPO; DERWE NT; IBM_TDB
35	L41	7	40 not (30 or 33 or 37)	EPO; JPO; DERWE NT; IBM_TDB

	L #	Hits	Search Text	DBs
1	L1	3489	((magnetic or mr or magneto or magnetoresist\$8) adj2 head).clm.	US-PGPUB
2	L2	28721	(resist or photoresist or photosensitiv\$8 or photopolymer\$8 or (photo or light or uv or ultraviolet) adj (sensitiv\$8 or polymer or polymeriz\$8 or polymeris\$8)).clm.	US-PGPUB
3	L3	32771	((first or second or two or additional\$6 or subsequent\$6) near3 (expos\$6 or radiat\$6 or irradiat\$6 or lithograph\$8 or photolithograph\$8 or mask or photomask or reticle)).clm.	US-PGPUB
4	L4	1026	(track near3 width).clm.	US-PGPUB
5	L5	18	1 and (2 with 3) and 4	US-PGPUB